L Number	Hits	Search Text	DB	Time stamp
1	11875	(pr photoresist photo?resist (photo near3	USPAT;	2004/09/30 15:14
		resist) resist) near10 (etch\$3 pattern4	US-PGPUB	
		trim\$4 remov\$3) near10 dry		
2	3636		USPAT;	2004/09/30 15:12
		resist) resist) near10 (etch\$3 pattern4	US-PGPUB	
		trim\$4 remov\$3) near10 dry) and		
		((hydrocarbon CH4 ("CH.sub.4")) and argon		
3	2	and oxygen "O.sub.2") ((pr photoresist photo?resist (photo near3	USPAT;	2004/09/30 15:08
] 3		resist) resist) near10 (etch\$3 pattern4	US-PGPUB	2004/09/30 15:08
		trim\$4 remov\$3) near10 dry) and	05 10105	
		((hydrocarbon CH4 ("CH.sub.4")) near5 argon		
		near5 (oxygen "O.sub.2"))		
4	21	((pr photoresist photo?resist (photo near3	USPAT;	2004/09/30 15:08
		resist) resist) near10 (etch\$3 pattern4	US-PGPUB	
		trim\$4 remov\$3) near10 dry) and		
		((hydrocarbon CH4 ("CH.sub.4")) with argon		
_		with (oxygen "O.sub.2"))		
5	5450	1 12 2	EPO; JPO;	2004/09/30 15:12
		resist) resist) near10 (etch\$3 pattern4	DERWENT;	
6	1	trim\$4 remov\$3) near10 dry ((pr photoresist photo?resist (photo near3	IBM_TDB EPO; JPO;	2004/09/30 15:12
0	_	resist) resist) near10 (etch\$3 pattern4	DERWENT;	2004/03/30 13:12
		trim\$4 remov\$3) near10 dry) and	IBM TDB	
		((hydrocarbon CH4 ("CH.sub.4")) and argon		
		and oxygen "O.sub.2")		
7	490	(hydrocarbon near3 gas) same (inert near3	USPAT;	2004/09/30 15:14
		gas) same (oxygen near3 gas)	US-PGPUB	
8	22		USPAT;	2004/09/30 15:15
		gas) same (oxygen near3 gas)) and ((pr	US-PGPUB	
		photoresist photo?resist (photo near3		
		resist) resist) near10 (etch\$3 pattern4		
_	325112	trim\$4 remov\$3)) pr photoresist photo?resist (photo near3	USPAT;	2004/06/21 14:56
	323112	resist) resist	US-PGPUB	2004/00/21 14:50
_	43155	· · · · · · · · · · · · · · · · · · ·	USPAT;	2004/06/21 14:56
		resist) resist) and ((gas plasma) same	US-PGPUB	,,
	1	(hydrocarbon oxygen inert))		
-	44173		USPAT;	2004/06/21 14:57
	1	resist) resist) and ((gas plasma) same ((CH4	US-PGPUB	
	†	"CH.sub.4" ("C" adj3 "H.sub.4")) (oxygen 02		
		"O.sub.2") (argon Ar "Ar")))		
-	53221		USPAT;	2004/06/21 11:39
		resist) resist) and ((gas plasma) same (hydrocarbon oxygen inert))) ((pr	US-PGPUB	
		hotoresist photo?resist (photo near3		
		resist) resist) and ((gas plasma) same ((CH4		
		"CH.sub.4" ("C" adj3 "H.sub.4")) (oxygen O2		
		"O.sub.2") (argon Ar "Ar"))))		
-	33206	(((pr photoresist photo?resist (photo near3	USPAT;	2004/06/21 14:57
		resist) resist) and ((gas plasma) same	US-PGPUB	
		(hydrocarbon oxygen inert))) ((pr		
		photoresist photo?resist (photo near3		
		resist) resist) and ((gas plasma) same ((CH4		
		"CH.sub.4" ("C" adj3 "H.sub.4")) (oxygen 02		
	Į.	"O.sub.2") (argon Ar "Ar"))))) and (etch\$3		
_	26375	<pre>pattern4 trim\$4) ((((pr photoresist photo?resist (photo near3))</pre>	USPAT;	2004/06/21 11:43
	203/3	resist) resist) and ((gas plasma) same	US-PGPUB	2004/00/21 11:43
		(hydrocarbon oxygen inert))) ((pr	33 13101	
		photoresist photo?resist (photo near3		
		resist) resist) and ((gas plasma) same ((CH4		
		"CH.sub.4" ("C" adj3 "H.sub.4")) (oxygen O2		
		"O.sub.2") (argon Ar "Ar"))))) and (etch\$3		
		pattern4 trim\$4)) and ((pr photoresist		
		photo?resist (photo near3 resist) resist)		
		same (etch\$3 pattern4 trim\$4))		

			T	10001/05/01 11
-	10795	The product of the second of t	USPAT;	2004/06/21 11:47
		near3 resist) resist) and ((gas plasma) same	US-PGPUB	
		(hydrocarbon oxygen inert))) ((pr		
		photoresist photo?resist (photo near3		
		resist) resist) and ((gas plasma) same ((CH4		
		"CH.sub.4" ("C" adj3 "H.sub.4")) (oxygen O2		
		"O.sub.2") (argon Ar "Ar"))))) and (etch\$3		
		pattern4 trim\$4)) and ((pr photoresist		
		photo?resist (photo near3 resist) resist)		
		same (etch\$3 pattern4 trim\$4))) and ((pr		
		photoresist photo?resist (photo near3		
		resist) resist) same (etch\$3 pattern4		
		trim\$4)) same ((gas plasma) same ((CH4		
		"CH.sub.4" ("C" adj3 "H.sub.4")) (oxygen O2		
		"O.sub.2") (argon Ar "Ar")))	_	
-	6173	· · · · · · · · · · · · · · · · · · ·	USPAT;	2004/06/21 11:45
		near3 resist) resist) and ((gas plasma) same	US-PGPUB	1
		(hydrocarbon oxygen inert))) ((pr		1
	:	photoresist photo?resist (photo near3		
1		resist) resist) and ((gas plasma) same ((CH4		
		"CH.sub.4" ("C" adj3 "H.sub.4")) (oxygen 02		
1		"O.sub.2") (argon Ar "Ar"))))) and (etch\$3		
[pattern4 trim\$4)) and ((pr photoresist		
	1	photo?resist (photo near3 resist) resist)		
		same (etch\$3 pattern4 trim\$4))) and ((pr		
		photoresist photo?resist (photo near3		
		resist) resist) same (etch\$3 pattern4		i
		trim\$4)) same ((gas plasma) same ((CH4	-	
		"CH.sub.4" ("C" adj3 "H.sub.4")) (oxygen O2		
1		"O.sub.2") (argon Ar "Ar")))) and flow		
-	6337	1 1 1 1 1 2	USPAT;	2004/06/21 11:45
		near3 resist) resist) and ((gas plasma) same	US-PGPUB	
		(hydrocarbon oxygen inert))) ((pr		
		photoresist photo?resist (photo near3		
		resist) resist) and ((gas plasma) same ((CH4		
		"CH.sub.4" ("C" adj3 "H.sub.4")) (oxygen 02		
		"O.sub.2") (argon Ar "Ar"))))) and (etch\$3		1
		pattern4 trim\$4)) and ((pr photoresist		1
		photo?resist (photo near3 resist) resist)		
		same (etch\$3 pattern4 trim\$4))) and ((pr		1
		photoresist photo?resist (photo near3		1
		resist) resist) same (etch\$3 pattern4		
		trim\$4)) same ((gas plasma) same ((CH4		
		"CH.sub.4" ("C" adj3 "H.sub.4")) (oxygen 02		
		"O.sub.2") (argon Ar "Ar")))) and (power		
		watt)	HODAE	2004/06/22 22 22
-	7436	((((((pr photoresist photo?resist (photo	USPAT;	2004/06/21 11:46
1		near3 resist) resist) and ((gas plasma) same	US-PGPUB	
		(hydrocarbon oxygen inert))) ((pr		
1		photoresist photo?resist (photo near3		
		resist) resist) and ((gas plasma) same ((CH4		
		"CH.sub.4" ("C" adj3 "H.sub.4")) (oxygen 02		
		"O.sub.2") (argon Ar "Ar"))))) and (etch\$3		
		pattern4 trim\$4)) and ((pr photoresist		
		photo?resist (photo near3 resist) resist)		
		same (etch\$3 pattern4 trim\$4))) and ((pr		
		photoresist photo?resist (photo near3 resist) resist) same (etch\$3 pattern4		
		trim\$4)) same ((gas plasma) same ((CH4		
		"CH.sub.4" ("C" adj3 "H.sub.4")) (oxygen 02		
	L.,,	"O.sub.2") (argon Ar "Ar")))) and pressure		

-	3924	(((((((pr photoresist photo?resist (photo	USPAT;	2004/06/21 11:46
		near3 resist) resist) and ((gas plasma) same	US-PGPUB	
	-	(hydrocarbon oxygen inert))) ((pr		
		photoresist photo?resist (photo near3		
		resist) resist) and ((gas plasma) same ((CH4		
		"CH.sub.4" ("C" adj3 "H.sub.4")) (oxygen O2		
		"O.sub.2") (argon Ar "Ar"))))) and (etch\$3		
		pattern4 trim\$4)) and ((pr photoresist		
		photo?resist (photo near3 resist) resist)		
		same (etch\$3 pattern4 trim\$4))) and ((pr		
		photoresist photo?resist (photo near3		
		resist) resist) same (etch\$3 pattern4		
		trim\$4)) same ((gas plasma) same ((CH4	·	•
		"CH.sub.4" ("C" adj3 "H.sub.4")) (oxygen O2		
		"O.sub.2") (argon Ar "Ar")))) and flow) and		
		((((((pr photoresist photo?resist (photo		
		near3 resist) resist) and ((gas plasma) same		
		(hydrocarbon oxygen inert))) ((pr		
		photoresist photo?resist (photo near3		
		resist) resist) and ((gas plasma) same ((CH4		·
		"CH.sub.4" ("C" adj3 "H.sub.4")) (oxygen O2	,	
		"O.sub.2") (argon Ar "Ar"))))) and (etch\$3		
	i	pattern4 trim\$4)) and ((pr photoresist		
		photo?resist (photo near3 resist) resist)		
		same (etch\$3 pattern4 trim\$4))) and ((pr	į	
		photoresist photo?resist (photo near3		
		resist) resist) same (etch\$3 pattern4		
		trim\$4)) same ((gas plasma) same ((CH4		
		"CH.sub.4" ("C" adj3 "H.sub.4")) (oxygen 02		
		"O.sub.2") (argon Ar "Ar")))) and (power		İ
		watt)) and ((((((pr photoresist		
	E	photo?resist (photo near3 resist) resist)		
		and ((gas plasma) same (hydrocarbon oxygen		
		inert))) ((pr photoresist photo?resist		!
		(photo near3 resist) resist) and ((gas		
		plasma) same ((CH4 "CH.sub.4" ("C" adj3		
		"H.sub.4")) (oxygen 02 "O.sub.2") (argon		
		Ar "Ar"))))) and (etch\$3 pattern4 trim\$4))		
		and ((pr photoresist photo?resist (photo near3 resist) resist) same (etch\$3 pattern4	1	
		trim\$4))) and ((pr photoresist photo?resist		
		(photo near3 resist) resist) same (etch\$3		
		pattern4 trim\$4)) same ((qas plasma) same		
		((CH4 "CH.sub.4" ("C" adj3 "H.sub.4"))	-	
		(cxygen 02 "0.sub.2") (argon Ar "Ar")))) and		
		pressure)	1	
	I	hrespare)		l

		Y	,	, ,
-	291	' ' ' ' ' ' ' ' ' ' ' ' ' ' ' ' ' ' '	USPAT;	2004/06/21 14:57
		near3 resist) resist) and ((gas plasma) same	US-PGPUB	
		(hydrocarbon oxygen inert))) ((pr		
		photoresist photo?resist (photo near3		
		resist) resist) and ((gas plasma) same ((CH4		
		"CH.sub.4" ("C" adj3 "H.sub.4")) (oxygen O2		
	1	"O.sub.2") (argon Ar "Ar"))))) and (etch\$3		
		pattern4 trim\$4)) and ((pr photoresist		
	1	photo?resist (photo near3 resist) resist)		
	1	same (etch\$3 pattern4 trim\$4))) and ((pr		
		photoresist photo?resist (photo near3		
		resist) resist) same (etch\$3 pattern4		
		trim\$4)) same ((gas plasma) same ((CH4		
		"CH.sub.4" ("C" adj3 "H.sub.4")) (oxygen O2		· ·
		"O.sub.2") (argon Ar "Ar")))) and flow) and		
	1	((((((pr photoresist photo?resist (photo		
		near3 resist) resist) and ((gas plasma) same		
		(hydrocarbon oxygen inert))) ((pr		
		photoresist photo?resist (photo near3		
		resist) resist) and ((gas plasma) same ((CH4		
		"CH.sub.4" ("C" adj3 "H.sub.4")) (oxygen O2		
		"O.sub.2") (argon Ar "Ar"))))) and (etch\$3		
		pattern4 trim\$4)) and ((pr photoresist		
		photo?resist (photo near3 resist) resist)		
		same (etch\$3 pattern4 trim\$4))) and ((pr		
		photoresist photo?resist (photo near3		
		resist) resist) same (etch\$3 pattern4		
		trim\$4)) same ((gas plasma) same ((CH4		
		"CH.sub.4" ("C" adj3 "H.sub.4")) (oxygen O2		
		"O.sub.2") (argon Ar "Ar")))) and (power		
		watt)) and ((((((pr photoresist		
İ		photo?resist (photo near3 resist) resist)		
	1	and ((gas plasma) same (hydrocarbon oxygen		
	[<pre>inert))) ((pr photoresist photo?resist</pre>		
	[(photo near3 resist) resist) and ((gas		
		plasma) same ((CH4 "CH.sub.4" ("C" adj3		
İ		"H.sub.4")) (oxygen O2 "O.sub.2") (argon		
		Ar "Ar"))))) and (etch\$3 pattern4 trim\$4))		
		and ((pr photoresist photo?resist (photo		
		near3 resist) resist) same (etch\$3 pattern4		
		trim\$4))) and ((pr photoresist photo?resist		
		(photo near3 resist) resist) same (etch\$3		
		pattern4 trim\$4)) same ((gas plasma) same		
		((CH4 "CH.sub.4" ("C" adj3 "H.sub.4"))		
		(oxygen 02 "0.sub.2") (argon Ar "Ar")))) and		
		pressure)) and ((CH4 "CH.sub.4" ("C" adj3		
		"H.sub.4")) and (oxygen O2 "O.sub.2") and		
		(argon Ar "Ar"))		

-	29 (((((((pr photoresist photo?resist (photo	USPAT;	2004/06/21 14:58
	near3 resist) resist) and ((gas plasma) same	US-PGPUB	
	(hydrocarbon oxygen inert))) ((pr		
	photoresist photo?resist (photo near3		
	resist) resist) and ((gas plasma) same ((CH4		
	"CH.sub.4" ("C" adj3 "H.sub.4")) (oxygen O2		
	"O.sub.2") (argon Ar "Ar"))))) and (etch\$3		
	pattern4 trim\$4)) and ((pr photoresist		
	<pre>photo?resist (photo near3 resist) resist)</pre>		
	same (etch\$3 pattern4 trim\$4))) and ((pr		
	photoresist photo?resist (photo near3		
	resist) resist) same (etch\$3 pattern4		
	trim\$4)) same ((gas plasma) same ((CH4		
	"CH.sub.4" ("C" adj3 "H.sub.4")) (oxygen O2		·
	"O.sub.2") (argon Ar "Ar")))) and flow) and		
	(((((((pr photoresist photo?resist (photo		!
	near3 resist) resist) and ((gas plasma) same		
	(hydrocarbon oxygen inert))) ((pr		
	photoresist photo?resist (photo near3		
	resist) resist) and ((gas plasma) same ((CH4		
	"CH.sub.4" ("C" adj3 "H.sub.4")) (oxygen 02		1
	"O.sub.2") (argon Ar "Ar"))))) and (etch\$3		
	pattern4 trim\$4)) and ((pr photoresist		
	<pre>photo?resist (photo near3 resist) resist)</pre>		[
	same (etch\$3 pattern4 trim\$4))) and ((pr		
	photoresist photo?resist (photo near3		
	resist) resist) same (etch\$3 pattern4		
	trim\$4)) same ((gas plasma) same ((CH4		
	"CH.sub.4" ("C" adj3 "H.sub.4")) (oxygen O2		
	"O.sub.2") (argon Ar "Ar")))) and (power		
	watt)) and ((((((pr photoresist		
İ	photo?resist (photo near3 resist) resist)		
	and ((gas plasma) same (hydrocarbon oxygen		
1	inert))) ((pr photoresist photo?resist		
	(photo near3 resist) resist) and ((qas		
	plasma) same ((CH4 "CH.sub.4" ("C" adj3		
	"H.sub.4")) (oxygen O2 "O.sub.2") (argon		i
	Ar "Ar"))))) and (etch\$3 pattern4 trim\$4))		
	and ((pr photoresist photo?resist (photo		
	near3 resist) resist) same (etch\$3 pattern4		
	trim\$4))) and ((pr photoresist photo?resist		
	(photo near3 resist) resist) same (etch\$3		
	pattern4 trim\$4)) same ((qas plasma) same		1
	((CH4 "CH.sub.4" ("C" adj3 "H.sub.4"))		1
			1
	(oxygen 02 "0.sub.2") (argon Ar "Ar")))) and		
	pressure)) and ((C2H6 ("C.sub.2" adj3		
	"H.sub.6")) and (oxygen O2 "O.sub.2") and (argon Ar "Ar"))		
l l	(algon Al "Al")	1	i l

near3 resist) resist photo?resist (photo near3 resist) resist) and ((gas plasma) same (hydrocarbon oxygen inert))) ((pr photoresist photo?resist (photo near3 resist) resist) and ((gas plasma) same ((CH4 "CH.sub.4" ("C" adj3 "H.sub.4")) (oxygen 02 "0.sub.2") (argon Ar "Ar")))) and (etch\$\frac{1}{3}\$ pattern4 trim\$\frac{1}{3}\$ pattern4 pattern4 trim\$\frac{1}{3}\$ pattern4 trim\$\frac{1}{3}\$ pattern4 pattern4 pattern4 pattern4 trim\$\frac{1}{3}\$ pattern4					
(hydrocarbon oxygen inert)) ((pr photoresist photo?resist (photo near3 resist) resist) and ((gas plasma) same ((CH4 "CH.sub.4" ("C" adj3 "H.sub.4")) (oxygen 02 "O.sub.2") (argon Ar "Ar")))) and (etch\$3 pattern4 trim\$4)) and ((pr photoresist photo?resist (photo near3 resist) resist) same (etch\$3 pattern4 trim\$4)) and ((pr photoresist photo?resist (photo near3 resist) resist) same (etch\$3 pattern4 trim\$4)) same ((gas plasma) same ((CH4 "CH.sub.4" ("C" adj3 "H.sub.4")) (oxygen 02 "O.sub.2") (argon Ar "Ar")))) and flow) and ((((((((f)photoresist photo?resist (photo near3 resist) resist) and ((gas plasma) same (hydrocarbon oxygen inert))) ((pr photoresist photo?resist (photo near3 resist) resist) and ((gas plasma) same ((CH4 "CH.sub.4" ("C" adj3 "H.sub.4")) (oxygen 02 "O.sub.2") (argon Ar "Ar")))) and (etch\$3 pattern4 trim\$4)) and ((pr photoresist photo?resist (photo near3 resist) resist) same (etch\$3 pattern4 trim\$4)) same ((gas plasma) same ((CH4 "CH.sub.4" ("C" adj3 "H.sub.4"))) (oxygen 02 "O.sub.2") (argon Ar "Ar")))) and ((pr photoresist photo?resist (photo near3 resist) resist) same (etch\$3 pattern4 trim\$4)) same ((gas plasma) same ((CH4 "CH.sub.4" ("C" adj3 "H.sub.4")) (oxygen 02 "O.sub.2") (argon Ar "Ar")))) and (power watt)) and (((((((pr photoresist photo?resist)) nad ((pr photoresist photo?resist (photo near3) resist) resist) resist) and (gas plasma) same ((CH4 "CH.sub.4" ("C" adj3 "H.sub.4")) (oxygen 02 "O.sub.2") (argon Ar "ari"))) and (power watt)) and (((((((pr photoresist photo?resist (photo near3) plasma) same ((PH "CH.sub.4") ("adj3 "H.sub.4"))) (oxygen 02 "O.sub.2") (argon Ar "Ar"))))) and (etch\$3 pattern4 trim\$4()) and (((pr photoresist photo?resist (photo	-	44	(((((((pr photoresist photo?resist (photo	USPAT;	2004/06/21 14:58
photoresist photo?resist (photo near3 resist) resist) and ((gas plasma) same ((CH4 "CH.sub.4" ("C" adj3"H.sub.4")) (oxygen O2 "O.sub.2") (argon Ar "Ar")))) and (etch\$3 pattern4 trim\$4\) and ((pr photoresist photo?resist (photo near3 resist) resist) same (etch\$3 pattern4 trim\$4\)) and ((pr photoresist photo?resist (photo near3 resist) resist) same (etch\$3 pattern4 trim\$4\) same ((gas plasma) same ((CH4 "CH.sub.4" ("C" adj3 "H.sub.4")) (oxygen O2 "O.sub.2") (argon Ar "Ar")))) and flow) and (((((((pr photoresist photo?resist (photo near3 resist) resist) and ((gas plasma) same (hydrocarbon oxygen inert))) ((pr photoresist photo?resist (photo near3 resist) resist) and ((gas plasma) same ((CH4 "CH.sub.4" ("C" adj3 "H.sub.4")) (oxygen O2 "O.sub.2") (argon Ar "Ar")))) and (etch\$3 pattern4 trim\$4\)) and ((pr photoresist photo?resist (photo near3 resist) resist) same (etch\$3 pattern4 trim\$4\))) and ((pr photoresist photo?resist (photo near3 resist) resist) same (etch\$3 pattern4 trim\$4\)) same ((gas plasma) same ((CH4 "CH.sub.4" ("C" adj3 "H.sub.4")) (oxygen O2 "O.sub.2") (argon Ar "Ar")))) and (power watt)) and ((((((((pr photoresist photo?resist photo?resist (photo near3 resist)) and ((gas plasma) same ((CH4 "CH.sub.4" ("C" adj3 "H.sub.4")) (oxygen O2 "O.sub.2") (argon Ar "Ar")))) and (power watt)) and ((((((((pr photoresist photo?resist (photo near3 resist)) and ((gas plasma) same ((CH4 "CH.sub.4" ("C" adj3" "H.sub.4")) (oxygen O2 "O.sub.2") (argon Ar "Ar"))))) and (etch\$3 pattern4 trim\$4\)) and ((pr photoresist photo?resist (photo			near3 resist) resist) and ((gas plasma) same	US-PGPUB	
photoresist photo?resist (photo near3 resist) resist) and ((gas plasma) same ((CH4 "CH.sub.4" ("C" adj3"H.sub.4")) (oxygen O2 "O.sub.2") (argon Ar "Ar")))) and (etch\$3 pattern4 trim\$4\) and ((pr photoresist photo?resist (photo near3 resist) resist) same (etch\$3 pattern4 trim\$4\)) and ((pr photoresist photo?resist (photo near3 resist) resist) same (etch\$3 pattern4 trim\$4\) same ((gas plasma) same ((CH4 "CH.sub.4" ("C" adj3 "H.sub.4")) (oxygen O2 "O.sub.2") (argon Ar "Ar")))) and flow) and (((((((pr photoresist photo?resist (photo near3 resist) resist) and ((gas plasma) same (hydrocarbon oxygen inert))) ((pr photoresist photo?resist (photo near3 resist) resist) and ((gas plasma) same ((CH4 "CH.sub.4" ("C" adj3 "H.sub.4")) (oxygen O2 "O.sub.2") (argon Ar "Ar")))) and (etch\$3 pattern4 trim\$4\)) and ((pr photoresist photo?resist (photo near3 resist) resist) same (etch\$3 pattern4 trim\$4\))) and ((pr photoresist photo?resist (photo near3 resist) resist) same (etch\$3 pattern4 trim\$4\)) same ((gas plasma) same ((CH4 "CH.sub.4" ("C" adj3 "H.sub.4")) (oxygen O2 "O.sub.2") (argon Ar "Ar")))) and (power watt)) and ((((((((pr photoresist photo?resist photo?resist (photo near3 resist)) and ((gas plasma) same ((CH4 "CH.sub.4" ("C" adj3 "H.sub.4")) (oxygen O2 "O.sub.2") (argon Ar "Ar")))) and (power watt)) and ((((((((pr photoresist photo?resist (photo near3 resist)) and ((gas plasma) same ((CH4 "CH.sub.4" ("C" adj3" "H.sub.4")) (oxygen O2 "O.sub.2") (argon Ar "Ar"))))) and (etch\$3 pattern4 trim\$4\)) and ((pr photoresist photo?resist (photo	į		(hydrocarbon oxygen inert))) ((pr		
resist) resist) and ((gas plasma) same ((CH4 "CH.sub.4" ("C" adj3"H.sub.4")))) and (etch\$3 pattern4 trim\$4)) and ((pr photoresist photo?resist (photo near3 resist) resist) same (etch\$3 pattern4 trim\$4))) and ((pr photoresist photo?resist (photo near3 resist) resist) same (etch\$3 pattern4 trim\$4)) same ((gas plasma) same ((CH4 "CH.sub.4" ("C" adj3"H.sub.4")) (oxygen 02 "0.sub.2") (argon Ar "Ar")))) and flow) and (((((((pr photoresist photo?resist (photo near3 resist) resist) and ((gas plasma) same ((hydrocarbon oxygen inert))) ((pr photoresist photo?resist (photo near3 resist) resist) and ((gas plasma) same ((CH4 "CH.sub.4" ("C" adj3"H.sub.4"))) (oxygen 02 "0.sub.2") (argon Ar "Ar")))) and (etch\$3 pattern4 trim\$4)) and ((pr photoresist photo?resist (photo near3 resist) resist) same (etch\$3 pattern4 trim\$4))) and ((pr photoresist photo?resist (photo near3 resist) resist) same (etch\$3 pattern4 trim\$4)) same ((gas plasma) same ((CH4 "CH.sub.4" ("C" adj3"H.sub.4")) (oxygen 02 "0.sub.2") (argon Ar "Ar")))) and (power watt)) and ((((((((pr photoresist photo?resist photo?resist (photo near3 resist) resist) and ((gas plasma) same ((CH4 "CH.sub.4" ("C" adj3"H.sub.4")) (oxygen 02 "0.sub.2") (argon Ar "Ar")))) and ((pas plasma) same ((CH4 "CH.sub.4" ("C" adj3"H.sub.4")) (oxygen 02 "0.sub.2") (argon Ar "Ar")))) and ((pas plasma) same ((CH4 "CH.sub.4" ("C" adj3"H.sub.4")) (oxygen 02 "0.sub.2") (argon Ar "Ar")))) and (power watt)) and (((((((pr photoresist photo?resist (photo near3) resist) resist) and ((pas plasma) same ((CH4 "CH.sub.4" ("C" adj3"H.sub.4")) and ((pr photoresist photo?resist (photo near3) "H.sub.4"))) (oxygen 02 "0.sub.2") (argon Ar "Ar"))))) and (etch\$3 pattern4 trim\$4)) and ((pr photoresist photo?resist (photo			photoresist photo?resist (photo near3		
"CH.sub.4" ("C" adj3 "H.sub.4")) (oxygen 02 "O.sub.2") (argon Ar "Ar")))) and (etch\$3 pattern4 trim\$4\)) and ((pr photoresist photo?resist (photo near3 resist) resist) same (etch\$3 pattern4 trim\$4\)) and ((pr photoresist photo?resist (photo near3 resist) resist) same (etch\$3 pattern4 trim\$4\)) same ((gas plasma) same ((CH4 "CH.sub.4" ("C" adj3 "H.sub.4")) (oxygen 02 "O.sub.2") (argon Ar "Ar")))) and flow) and (((((((pr photoresist photo?resist (photo near3 resist) resist) and ((gas plasma) same ((hydrocarbon oxygen inert))) ((pr photoresist photo?resist (photo near3 resist) resist) and ((gas plasma) same ((CH4 "CH.sub.4" ("C" adj3 "H.sub.4")) (oxygen 02 "O.sub.2") (argon Ar "Ar")))) and (etch\$3 pattern4 trim\$4\)) and ((pr photoresist photo?resist (photo near3 resist) resist) same (etch\$3 pattern4 trim\$4\)) and ((pr photoresist photo?resist (photo near3 resist) resist) same (etch\$3 pattern4 trim\$4\)) same ((gas plasma) same ((CH4 "CH.sub.4" ("C" adj3 "H.sub.4")) (oxygen 02 "O.sub.2") (argon Ar "Ar")))) and (power watt)) and ((((((((pr) photoresist photo?resist photo?resist (photo near3 resist) resist) and ((gas plasma) same ((CH4 "CH.sub.4" ("C" adj3 "H.sub.4")) (oxygen 02 "O.sub.2") (argon Ar "Ar")))) and (power watt)) and ((((((((((pr) photoresist photo?resist (photo near3 resist) resist) and ((gas plasma) same (hydrocarbon oxygen inert)) ((pr photoresist photo?resist (photo near3 resist) resist) and ((gas plasma) same (CH4 "CH.sub.4" ("C" adj3 "H.sub.4")) (oxygen 02 "O.sub.2") (argon Ar "Ar"))))) and (etch\$3 pattern4 trim\$4)) and ((pr photoresist photo?resist (photo	ļ				
pattern4 trim\$4) and ((pr photoresist photo?resist (photo near3 resist) resist) same (etch\$3 pattern4 trim\$4)) and ((pr photoresist photo?resist (photo near3 resist) resist) same (etch\$3 pattern4 trim\$4)) and ((pr photoresist photo?resist (photo near3 resist) resist) same (etch\$3 pattern4 trim\$4)) same ((gas plasma) same ((CH4 "CH. sub.4" ("C" adj3 "H. sub.4")) (oxygen O2 "O. sub.2") (argon Ar "Ar")))) and flow) and (((((((pr photoresist photo?resist (photo near3 resist) resist) and ((gas plasma) same (hydrocarbon oxygen inert))) ((pr photoresist photo?resist (photo near3 resist) resist) and ((gas plasma) same ((CH4 "CH. sub.4" ("C" adj3 "H. sub.4")) (oxygen O2 "O. sub.2") (argon Ar "Ar")))) and (etch\$3 pattern4 trim\$4)) and ((pr photoresist photo?resist (photo near3 resist) resist) same (etch\$3 pattern4 trim\$4)) and ((pr photoresist photo?resist (photo near3 resist) resist) resist) same (etch\$3 pattern4 trim\$4)) same ((GH4 "CH. sub.4" ("C" adj3 "H. sub.4")) (oxygen O2 "O. sub.2") (argon Ar "Ar")))) and (power watt)) and (((((((pr photoresist photo?resist) resist)					l i
pattern4 trim\$4)) and ((pr photoresist photo?resist (photo near3 resist) resist) same (etch\$3 pattern4 trim\$4))) and ((pr photoresist photo?resist (photo near3 resist) resist) resist) same (etch\$3 pattern4 trim\$4)) same ((gas plasma) same ((CH4 "CH.sub.4" ("C" adj3 "H.sub.4")) (oxygen O2 "O.sub.2") (argon Ar "Ar")))) and flow) and (((((((((((pr photoresist photo?resist (photo near3 resist) resist) and ((gas plasma) same (hydrocarbon oxygen inert))) ((pr photoresist photo?resist (photo near3 resist) resist) and ((gas plasma) same ((CH4 "CH.sub.4" ("C" adj3 "H.sub.4")) (oxygen O2 "O.sub.2") (argon Ar "Ar")))) and (etch\$3 pattern4 trim\$4)) and ((pr photoresist photo?resist (photo near3 resist) resist) same (etch\$3 pattern4 trim\$4)) and ((pr photoresist photo?resist (photo near3 resist) resist) same (etch\$3 pattern4 trim\$4)) same ((CH4 "CH.sub.4" ("C" adj3 "H.sub.4")) (oxygen O2 "O.sub.2") (argon Ar "Ar")))) and (power watt)) and (((((((pr photoresist photo?resist (photo near3 resist) resist) same ((((H4 "CH.sub.4" ("C" adj3 "H.sub.4")) (oxygen O2 "O.sub.2") (argon Ar "Ar")))) and (power watt)) and (((((((pr photoresist photo?resist (photo near3 resist) resist) photo?resist (photo near3 resist) resist) photo?resist (photo near3 resist) resist) and ((gas plasma) same ((H4 "CH.sub.4" ("C" adj3 "H.sub.4")) (argon Ar "Ar")))) (argon Ar "Ar"))))) and (etch\$3 pattern4 trim\$4)) and ((Pr photoresist photo?resist (photo near3 resist) resist) and ((gas plasma) same ((H4 "CH.sub.4" ("C" adj3 "H.sub.4")) (argon Ar "Ar"))))) and (etch\$3 pattern4 trim\$4)) and ((pr photoresist photo?resist (photo	ļ		"O.sub.2") (argon Ar "Ar"))))) and (etch\$3		
photo?resist (photo near3 resist) resist) same (etch\$3 pattern4 trim\$4))) and ((pr photoresist photo?resist (photo near3 resist) resist) same (etch\$3 pattern4 trim\$4)) same ((gas plasma) same ((CH4 "CH.sub.4" ("C" adj3 "H.sub.4")) (oxygen 02 "O.sub.2") (argon Ar "Ar")))) and flow) and (((((((pr) photoresist photo?resist (photo near3 resist) resist) and ((gas plasma) same (hydrocarbon oxygen inert))) ((pr photoresist) photo?resist (photo near3 resist) resist) and ((gas plasma) same ((CH4 "CH.sub.4" ("C" adj3 "H.sub.4")) (oxygen 02 "O.sub.2") (argon Ar "Ar")))) and (etch\$3 pattern4 trim\$4)) and ((pr photoresist photo?resist (photo near3 resist) resist) same (etch\$3 pattern4 trim\$4))) and ((pr photoresist photo?resist (photo near3 resist) resist) same (etch\$3 pattern4 trim\$4)) same ((gas plasma) same ((CH4 "CH.sub.4" ("C" adj3 "H.sub.4")) (oxygen 02 "O.sub.2") (argon Ar "Ar")))) and (power watt)) and (((((((pr photoresist photo?resist (photo near3 resist) resist) and ((gas plasma) same (hydrocarbon oxygen inert))) ((pr photoresist photo?resist (photo near3 resist) resist) and (gas plasma) same (hydrocarbon oxygen inert))) ((pr photoresist photo?resist (photo near3 resist) resist) and ((gas plasma) same ((CH4 "CH.sub.4" ("C" adj3 "H.sub.4")) (oxygen 02 "O.sub.2") (argon Ar "Ar"))))) and (etch\$3 pattern4 trim\$4)) and ((pr photoresist photo?resist (photo					
same (etch\$3 pattern4 trim\$41)) and ((pr photoresist photo?resist (photo near3 resist) resist) same (etch\$3 pattern4 trim\$41) same ((gas plasma) same ((CH4 "CH.sub.4" ("C" adj3 "H.sub.4")) (oxygen O2 "O.sub.2") (argon Ar "Ar"))) and flow) and (((((((((pr photoresist photo?resist (photo near3 resist) resist) and ((gas plasma) same (hydrocarbon oxygen inert))) ((pr photoresist photo?resist (photo near3 resist) resist) and ((gas plasma) same ((CH4 "CH.sub.4" ("C" adj3 "H.sub.4")) (oxygen O2 "O.sub.2") (argon Ar "Ar")))) and (etch\$3 pattern4 trim\$41) and ((pr photoresist photo?resist (photo near3 resist) resist) same (etch\$3 pattern4 trim\$41)) and ((pr photoresist photo?resist (photo near3 resist) resist) same (etch\$3 pattern4 trim\$41)) and ((pr photoresist proto?resist (photo near3 resist) resist) resist) resist) resist) same ((CH4 "CH.sub.4" ("C" adj3 "H.sub.4")) (oxygen O2 "O.sub.2") (argon Ar "Ar")))) and (power watt)) and (((((((pr photoresist photo?resist photo?resist photo?resist (photo near3 resist) resist) and ((gas plasma) same (hydrocarbon oxygen inert))) ((pr photoresist photo?resist (photo near3 resist) resist) and ((gas plasma) same (near3 resist) resist) and ((gas plasma) same (hydrocarbon oxygen inert))) ((pr photoresist photo?resist (photo near3 resist) resist) and ((gas plasma) same (near3 resist) resist) and ((gas plasm					
photoresist photo?resist (photo near3 resist) resist) same (etch\$3 pattern4 trim\$4)) same ((gas plasma) same ((CH4 "CH.sub.4" ("C" adj3 "H.sub.4")) (oxygen O2 "O.sub.2") (argon Ar "Ar")))) and flow) and (((((((pr) photoresist photo?resist (photo near3 resist) resist) and ((gas plasma) same (hydrocarbon oxygen inert)) ((pr photoresist photo?resist (photo near3 resist) resist) and ((gas plasma) same ((CH4 "CH.sub.4" ("C" adj3 "H.sub.4")) (oxygen O2 "O.sub.2") (argon Ar "Ar"))))) and (etch\$3 pattern4 trim\$4)) and ((pr photoresist photo?resist (photo near3 resist) resist) same (etch\$3 pattern4 trim\$4))) and ((pr photoresist photo?resist (photo near3 resist) resist) same (etch\$3 pattern4 trim\$4)) same ((gas plasma) same ((CH4 "CH.sub.4" ("C" adj3 "H.sub.4")) (oxygen O2 "O.sub.2") (argon Ar "Ar")))) and (power watt)) and ((((((pr) photoresist photo?resist (photo near3 resist) resist) and ((gas plasma) same (hydrocarbon oxygen inert))) ((pr photoresist photo?resist (photo near3 resist) resist) and ((gas plasma) same (hydrocarbon oxygen inert))) ((pr photoresist photo?resist (photo near3 resist) resist) and ((gas plasma) same ((CH4 "CH.sub.4" ("C" adj3 "H.sub.4")) (oxygen O2 "O.sub.2") (argon Ar "Ar")))) and (etch\$3 pattern4 trim\$4)) and ((pr photoresist photo?resist (photo	1		1.7		
resist) resist) same (etch\$3 pattern4 trim\$4)) same ((gas plasma) same ((CH4 "CH.sub.4" ("C" adj3" H.sub.4")) (oxygen O2 "O.sub.2") (argon Ar "Ar")))) and flow) and (((((((fp photoresist photo?resist (photo near3 resist) resist) and ((gas plasma) same (hydrocarbon oxygen inert))) ((pr photoresist photo?resist (photo near3 resist) resist) and ((gas plasma) same ((CH4 "CH.sub.4" ("C" adj3 "H.sub.4")) (oxygen O2 "O.sub.2") (argon Ar "Ar")))) and (etch\$3 pattern4 trim\$4)) and ((pr photoresist photo?resist (photo near3 resist) resist) same (etch\$3 pattern4 trim\$4))) and ((pr photoresist photo?resist (photo near3 resist) resist) same (etch\$3 pattern4 trim\$4)) same ((gas plasma) same ((CH4 "CH.sub.4" ("C" adj3 "H.sub.4")) (oxygen O2 "O.sub.2") (argon Ar "Ar")))) and (power watt)) and (((((((pr photoresist photo?resist (photo near3 resist) resist) and ((gas plasma) same (hydrocarbon oxygen inert))) ((pr photoresist photo?resist (photo near3 resist) resist) and ((gas plasma) same (hydrocarbon oxygen inert))) ((pr photoresist photo?resist (photo near3 resist) resist) and ((gas plasma) same ((CH4 "CH.sub.4" ("C" adj3 "H.sub.4")) (oxygen O2 "O.sub.2") (argon Ar "Ar")))) and (etch\$3 pattern4 trim\$4)) and ((pr photoresist photo?resist (photo			_ · · · · · · · · · · · · · · · · · · ·		
trim\$4)) same ((gas plasma) same ((CH4 "CH.sub.4" ("C" adj3 "H.sub.4")) (oxygen O2 "O.sub.2") (argon Ar "Ar"))) and flow) and (((((((pr photoresist photo?resist (photo near3 resist) resist) and ((gas plasma) same (hydrocarbon oxygen inert))) ((pr photoresist photo?resist (photo near3 resist) resist) and ((gas plasma) same ((CH4 "CH.sub.4" ("C" adj3 "H.sub.4")) (oxygen O2 "O.sub.2") (argon Ar "Ar")))) and (etch\$3 pattern4 trim\$4)) and ((pr photoresist photo?resist (photo near3 resist) resist) same (etch\$3 pattern4 trim\$4)) and ((pr photoresist same (etch\$3 pattern4 trim\$4))) and ((CH4 "CH.sub.4" ("C" adj3 "H.sub.4")) (oxygen O2 "O.sub.2") (argon Ar "Ar")))) and (power watt)) and ((((((pr photoresist photo?resist (photo near3 resist) resist) and ((gas plasma) same ((CH4 "CH.sub.4" ("C" adj3 "H.sub.4")) (oxygen O2 "O.sub.2") (argon Ar "Ar")))) and (gas plasma) same (hydrocarbon oxygen inert))) ((pr photoresist photo?resist (photo near3 resist) resist) and ((gas plasma) same ((CH4 "CH.sub.4" ("C" adj3 "H.sub.4")) (oxygen O2 "O.sub.2") (argon Ar "Ar")))) and (etch\$3 pattern4 trim\$4)) and ((pr photoresist photo?resist (photo near3 resist) resist) and (resist) and	į		• • • •		
"CH.sub.4" ("C" adj3 "H.sub.4")) (oxygen O2 "O.sub.2") (argon Ar "Ar"))) and flow) and (((((((pr photoresist photo?resist (photo near3 resist) resist) and ((gas plasma) same (hydrocarbon oxygen inert))) ((pr photoresist photo?resist (photo near3 resist) resist) and ((gas plasma) same ((CH4 "CH.sub.4" ("C" adj3 "H.sub.4")) (oxygen O2 "O.sub.2") (argon Ar "Ar")))) and (etch\$3 pattern4 trim\$4)) and ((pr photoresist photo?resist (photo near3 resist) resist) same (etch\$3 pattern4 trim\$4))) and ((pr photoresist photo?resist (photo near3 resist) resist) same (etch\$3 pattern4 trim\$4)) same ((gas plasma) same ((CH4 "CH.sub.4" ("C" adj3 "H.sub.4")) (oxygen O2 "O.sub.2") (argon Ar "Ar")))) and (power watt)) and (((((((pr photoresist photo?resist (photo near3 resist) resist) and ((gas plasma) same (hydrocarbon oxygen inert))) ((pr photoresist photo?resist (photo near3 resist) resist) and ((gas plasma) same ((CH4 "CH.sub.4" ("C" adj3 "H.sub.4")) (oxygen O2 "O.sub.2") (argon Ar "Ar"))))) and etch\$3 pattern4 trim\$4)) and ((pr photoresist photo?resist (photo			· · · · · · · · · · · · · · · · · · ·		
"O.sub.2") (argon Ar "Ar")))) and flow) and (((((((pr photoresist photo?resist (photo near3 resist) resist) and ((gas plasma) same (hydrocarbon oxygen inert))) ((pr photoresist photo?resist (photo near3 resist) resist) and ((gas plasma) same ((CH4 "CH.sub.4" ("C" adj3 "H.sub.4")) (oxygen O2 "O.sub.2") (argon Ar "Ar")))) and (etch\$3 pattern4 trim\$4)) and ((pr photoresist photo?resist (photo near3 resist) resist) same (etch\$3 pattern4 trim\$4))) and ((pr photoresist photo?resist (photo near3 resist) resist) same (etch\$3 pattern4 trim\$4)) same ((gas plasma) same ((CH4 "CH.sub.4" ("C" adj3 "H.sub.4")) (oxygen O2 "O.sub.2") (argon Ar "Ar")))) and (power watt)) and ((((((pr photoresist photo?resist (photo near3 resist) resist) and ((gas plasma) same (hydrocarbon oxygen inert))) ((pr photoresist photo?resist (photo near3 resist) resist) and ((gas plasma) same ((CH4 "CH.sub.4" ("C" adj3 "H.sub.4")) (oxygen O2 "O.sub.2") (argon Ar "Ar"))))) and (etch\$3 pattern4 trim\$4)) and (((pr photoresist photo?resist (photo					
<pre>(((((((((pr photoresist photo?resist (photo near3 resist) resist) and ((gas plasma) same (hydrocarbon oxygen inert))) ((pr photoresist photo?resist (photo near3 resist) resist) and ((gas plasma) same ((CH4 "CH.sub.4" ("C" adj3 "H.sub.4")) (oxygen O2 "O.sub.2") (argon Ar "Ar")))) and (etch\$3 pattern4 trim\$4\) and ((pr photoresist photo?resist (photo near3 resist) resist) same (etch\$3 pattern4 trim\$4\)) and ((pr photoresist photo?resist (photo near3 resist) resist) same (etch\$3 pattern4 trim\$4\) same ((gas plasma) same ((CH4 "CH.sub.4" ("C" adj3 "H.sub.4")) (oxygen O2 "O.sub.2") (argon Ar "Ar"))) and (power watt)) and (((((((pr photoresist photo?resist (photo near3 resist) resist) and ((gas plasma) same (hydrocarbon oxygen inert))) ((pr photoresist (photo near3 resist) resist) and ((gas plasma) same ((CH4 "CH.sub.4" ("C" adj3 "H.sub.4")))) and (etch\$3 pattern4 trim\$4\) and ((pr photoresist photo?resist (photo</pre>					
near3 resist) resist) and ((gas plasma) same (hydrocarbon oxygen inert))) ((pr photoresist photo?resist (photo near3 resist) resist) and ((gas plasma) same ((CH4 "CH.sub.4" ("C" adj3 "H.sub.4")) (oxygen O2 "O.sub.2") (argon Ar "Ar")))) and (etch\$3 pattern4 trim\$4\)) and ((pr photoresist photo?resist (photo near3 resist) resist) same (etch\$3 pattern4 trim\$4\)) and ((pr photoresist photo?resist (photo near3 resist) resist) same (etch\$3 pattern4 trim\$4\)) same ((gas plasma) same ((CH4 "CH.sub.4" ("C" adj3 "H.sub.4")) (oxygen O2 "O.sub.2") (argon Ar "Ar"))) and (power watt)) and ((((((pr photoresist photo?resist (photo near3 resist) resist) and ((gas plasma) same (hydrocarbon oxygen inert))) ((pr photoresist photo?resist (photo near3 resist) resist) (photo near3 resist) resist) and ((gas plasma) same (rud "CH.sub.4" ("C" adj3 "H.sub.4"))) (oxygen O2 "O.sub.2") (argon Ar "Ar"))))) and (etch\$3 pattern4 trim\$4)) and ((pr photoresist photo?resist (photo					
<pre>(hydrocarbon oxygen inert))) ((pr photoresist photo?resist (photo near3 resist) resist) and ((gas plasma) same ((CH4 "CH.sub.4" ("C" adj3 "H.sub.4")) (oxygen O2 "O.sub.2") (argon Ar "Ar"))))) and (etch\$3 pattern4 trim\$4\)) and ((pr photoresist photo?resist (photo near3 resist) resist) same (etch\$3 pattern4 trim\$4\)) and ((pr photoresist photo?resist (photo near3 resist) resist) same (etch\$3 pattern4 trim\$4\)) same ((gas plasma) same ((CH4 "CH.sub.4" ("C" adj3 "H.sub.4")) (oxygen O2 "O.sub.2") (argon Ar "Ar")))) and (power watt)) and (((((((pr photoresist photo?resist (photo near3 resist) resist) and ((gas plasma) same (hydrocarbon oxygen inert))) ((pr photoresist photo?resist (photo near3 resist) resist) and ((gas plasma) same ((CH4 "CH.sub.4" ("C" adj3 "H.sub.4")) (oxygen O2 "O.sub.2") (argon Ar "Ar")))) and (etch\$3 pattern4 trim\$4\)) and ((pr photoresist photo?resist (photo</pre>		1	I		
photoresist photo?resist (photo near3 resist) resist) and ((gas plasma) same ((CH4 "CH.sub.4" ("C" adj3 "H.sub.4")) (oxygen 02 "O.sub.2") (argon Ar "Ar")))) and (etch\$3 pattern4 trim\$4)) and ((pr photoresist photo?resist (photo near3 resist) resist) same (etch\$3 pattern4 trim\$4)) and ((pr photoresist photo?resist (photo near3 resist) resist) same (etch\$3 pattern4 trim\$4)) same ((gas plasma) same ((CH4 "CH.sub.4" ("C" adj3 "H.sub.4")) (oxygen 02 "O.sub.2") (argon Ar "Ar")))) and (power watt)) and ((((((pr photoresist photo?resist (photo near3 resist) resist) and ((gas plasma) same (hydrocarbon oxygen inert))) ((pr photoresist photo?resist (photo near3 resist) resist) and ((gas plasma) same ((CH4 "CH.sub.4" ("C" adj3 "H.sub.4")) (oxygen 02 "O.sub.2") (argon Ar "Ar"))))) and (etch\$3 pattern4 trim\$4)) and ((pr photoresist photo?resist (photo					
resist) resist) and ((gas plasma) same ((CH4 "CH.sub.4" ("C" adj3 "H.sub.4")) (oxygen O2 "O.sub.2") (argon Ar "Ar"))))) and (etch\$3 pattern4 trim\$4)) and ((pr photoresist photo?resist (photo near3 resist) resist) same (etch\$3 pattern4 trim\$4)) and ((pr photoresist photo?resist (photo near3 resist) resist) same (etch\$3 pattern4 trim\$4)) same ((gas plasma) same ((CH4 "CH.sub.4" ("C" adj3 "H.sub.4")) (oxygen O2 "O.sub.2") (argon Ar "Ar")))) and (power watt)) and ((((((pr photoresist photo?resist (photo near3 resist) resist) and ((gas plasma) same (hydrocarbon oxygen inert))) ((pr photoresist photo?resist (photo near3 resist) resist) and ((gas plasma) same ((CH4 "CH.sub.4" ("C" adj3 "H.sub.4")) (oxygen O2 "O.sub.2") (argon Ar "Ar"))))) and (etch\$3 pattern4 trim\$4)) and ((pr photoresist photo?resist (photo					i
"CH.sub.4" ("C" adj3 "H.sub.4")) (oxygen O2 "O.sub.2") (argon Ar "Ar")))) and (etch\$3 pattern4 trim\$4)) and ((pr photoresist photo?resist (photo near3 resist) resist) same (etch\$3 pattern4 trim\$4)) and ((pr photoresist photo?resist (photo near3 resist) resist) same (etch\$3 pattern4 trim\$4)) same ((gas plasma) same ((CH4 "CH.sub.4" ("C" adj3 "H.sub.4")) (oxygen O2 "O.sub.2") (argon Ar "Ar")))) and (power watt)) and ((((((pr photoresist photo?resist (photo near3 resist) resist) and ((gas plasma) same (hydrocarbon oxygen inert))) ((pr photoresist photo?resist (photo near3 resist) resist) and ((gas plasma) same ((CH4 "CH.sub.4" ("C" adj3 "H.sub.4")) (oxygen O2 "O.sub.2") (argon Ar "Ar")))) and (etch\$3 pattern4 trim\$4)) and ((pr photoresist photo?resist (photo					
"O.sub.2") (argon Ar "Ar")))) and (etch\$3 pattern4 trim\$4)) and ((pr photoresist photo?resist (photo near3 resist) resist) same (etch\$3 pattern4 trim\$4)) and ((pr photoresist photo?resist (photo near3 resist) resist) same (etch\$3 pattern4 trim\$4)) same ((gas plasma) same ((CH4 "CH.sub.4" ("C" adj3 "H.sub.4")) (oxygen O2 "O.sub.2") (argon Ar "Ar")))) and (power watt)) and ((((((pr photoresist photo?resist (photo near3 resist) resist) and ((gas plasma) same (hydrocarbon oxygen inert))) ((pr photoresist photo?resist (photo near3 resist) resist) and ((gas plasma) same ((CH4 "CH.sub.4" ("C" adj3 "H.sub.4")) (oxygen O2 "O.sub.2") (argon Ar "Ar"))))) and (etch\$3 pattern4 trim\$4)) and ((pr photoresist photo?resist (photo					l i
<pre>pattern4 trim\$4) and ((pr photoresist photo?resist (photo near3 resist) resist) same (etch\$3 pattern4 trim\$4))) and ((pr photoresist photo?resist (photo near3 resist) resist) same (etch\$3 pattern4 trim\$4)) same ((gas plasma) same ((CH4 "CH.sub.4" ("C" adj3 "H.sub.4")) (oxygen O2 "O.sub.2") (argon Ar "Ar")))) and (power watt)) and (((((((pr photoresist photo?resist (photo near3 resist) resist) and ((gas plasma) same (hydrocarbon oxygen inert))) ((pr photoresist photo?resist (photo near3 resist) resist) and ((gas plasma) same ((CH4 "CH.sub.4" ("C" adj3 "H.sub.4")) (oxygen O2 "O.sub.2") (argon Ar "Ar"))))) and (etch\$3 pattern4 trim\$4)) and ((pr photoresist photo?resist (photo</pre>					
photo?resist (photo near3 resist) resist) same (etch\$3 pattern4 trim\$4)) and ((pr photoresist photo?resist (photo near3 resist) resist) same (etch\$3 pattern4 trim\$4)) same ((gas plasma) same ((CH4 "CH.sub.4" ("C" adj3 "H.sub.4")) (oxygen O2 "O.sub.2") (argon Ar "Ar")))) and (power watt)) and (((((((pr photoresist photo?resist (photo near3 resist) resist) and ((gas plasma) same (hydrocarbon oxygen inert))) ((pr photoresist photo?resist (photo near3 resist) resist) and ((gas plasma) same ((CH4 "CH.sub.4" ("C" adj3 "H.sub.4")) (oxygen O2 "O.sub.2") (argon Ar "Ar"))))) and (etch\$3 pattern4 trim\$4)) and ((pr photoresist photo?resist (photo					
same (etch\$3 pattern4 trim\$4)) and ((pr photoresist photo?resist (photo near3 resist) resist) same (etch\$3 pattern4 trim\$4)) same ((gas plasma) same ((CH4 "CH.sub.4" ("C" adj3 "H.sub.4")) (oxygen O2 "O.sub.2") (argon Ar "Ar")))) and (power watt)) and (((((((pr photoresist photo?resist (photo near3 resist) resist) and ((gas plasma) same (hydrocarbon oxygen inert))) ((pr photoresist photo?resist (photo near3 resist) resist) and ((gas plasma) same ((CH4 "CH.sub.4" ("C" adj3 "H.sub.4")) (oxygen O2 "O.sub.2") (argon Ar "Ar"))))) and (etch\$3 pattern4 trim\$4)) and ((pr photoresist photo?resist (photo					
photoresist photo?resist (photo near3 resist) resist) same (etch\$3 pattern4 trim\$4)) same ((gas plasma) same ((CH4 "CH.sub.4" ("C" adj3 "H.sub.4")) (oxygen O2 "O.sub.2") (argon Ar "Ar")))) and (power watt)) and ((((((pr photoresist photo?resist (photo near3 resist) resist) and ((gas plasma) same (hydrocarbon oxygen inert))) ((pr photoresist photo?resist (photo near3 resist) resist) and ((gas plasma) same ((CH4 "CH.sub.4" ("C" adj3 "H.sub.4")) (oxygen O2 "O.sub.2") (argon Ar "Ar"))))) and (etch\$3 pattern4 trim\$4)) and ((pr photoresist photo?resist (photo					·
resist) resist) same (etch\$3 pattern4 trim\$4)) same ((gas plasma) same ((CH4 "CH.sub.4" ("C" adj3 "H.sub.4")) (oxygen O2 "O.sub.2") (argon Ar "Ar")))) and (power watt)) and ((((((pr photoresist photo?resist (photo near3 resist) resist) and ((gas plasma) same (hydrocarbon oxygen inert))) ((pr photoresist photo?resist (photo near3 resist) resist) and ((gas plasma) same ((CH4 "CH.sub.4" ("C" adj3 "H.sub.4")) (oxygen O2 "O.sub.2") (argon Ar "Ar"))))) and (etch\$3 pattern4 trim\$4)) and ((pr photoresist photo?resist (photo					
trim\$4)) same ((gas plasma) same ((CH4 "CH.sub.4" ("C" adj3 "H.sub.4")) (oxygen O2 "O.sub.2") (argon Ar "Ar")))) and (power watt)) and ((((((pr photoresist photo?resist (photo near3 resist) resist) and ((gas plasma) same (hydrocarbon oxygen inert))) ((pr photoresist photo?resist (photo near3 resist) resist) and ((gas plasma) same ((CH4 "CH.sub.4" ("C" adj3 "H.sub.4")) (oxygen O2 "O.sub.2") (argon Ar "Ar"))))) and (etch\$3 pattern4 trim\$4)) and ((pr photoresist photo?resist (photo			,		
"CH.sub.4" ("C" adj3 "H.sub.4")) (oxygen O2 "O.sub.2") (argon Ar "Ar")))) and (power watt)) and ((((((pr photoresist photo?resist (photo near3 resist) resist) and ((gas plasma) same (hydrocarbon oxygen inert))) ((pr photoresist photo?resist (photo near3 resist) resist) and ((gas plasma) same ((CH4 "CH.sub.4" ("C" adj3 "H.sub.4")) (oxygen O2 "O.sub.2") (argon Ar "Ar"))))) and (etch\$3 pattern4 trim\$4)) and ((pr photoresist photo?resist (photo					
"O.sub.2") (argon Ar "Ar")))) and (power watt)) and (((((((pr photoresist photo?resist (photo near3 resist) resist) and ((gas plasma) same (hydrocarbon oxygen inert))) ((pr photoresist photo?resist (photo near3 resist) resist) and ((gas plasma) same ((CH4 "CH.sub.4" ("C" adj3 "H.sub.4")) (oxygen O2 "O.sub.2") (argon Ar "Ar"))))) and (etch\$3 pattern4 trim\$4)) and ((pr photoresist photo?resist (photo			,		
<pre>watt)) and (((((((pr photoresist photo?resist (photo near3 resist) resist) and ((gas plasma) same (hydrocarbon oxygen inert))) ((pr photoresist photo?resist (photo near3 resist) resist) and ((gas plasma) same ((CH4 "CH.sub.4" ("C" adj3 "H.sub.4")) (oxygen O2 "O.sub.2") (argon Ar "Ar"))))) and (etch\$3 pattern4 trim\$4)) and ((pr photoresist photo?resist (photo</pre>					
photo?resist (photo near3 resist) resist) and ((gas plasma) same (hydrocarbon oxygen inert))) ((pr photoresist photo?resist (photo near3 resist) resist) and ((gas plasma) same ((CH4 "CH.sub.4" ("C" adj3 "H.sub.4")) (oxygen O2 "O.sub.2") (argon Ar "Ar"))))) and (etch\$3 pattern4 trim\$4)) and ((pr photoresist photo?resist (photo		}			
and ((gas plasma) same (hydrocarbon oxygen inert))) ((pr photoresist photo?resist (photo near3 resist) resist) and ((gas plasma) same ((CH4 "CH.sub.4" ("C" adj3 "H.sub.4")) (oxygen O2 "O.sub.2") (argon Ar "Ar"))))) and (etch\$3 pattern4 trim\$4)) and ((pr photoresist photo?resist (photo					
<pre>inert))) ((pr photoresist photo?resist (photo near3 resist) resist) and ((gas plasma) same ((CH4 "CH.sub.4" ("C" adj3 "H.sub.4")) (oxygen O2 "O.sub.2") (argon Ar "Ar"))))) and (etch\$3 pattern4 trim\$4)) and ((pr photoresist photo?resist (photo</pre>					
<pre>(photo near3 resist) resist) and ((gas plasma) same ((CH4 "CH.sub.4" ("C" adj3 "H.sub.4")) (oxygen O2 "O.sub.2") (argon Ar "Ar"))))) and (etch\$3 pattern4 trim\$4)) and ((pr photoresist photo?resist (photo</pre>					
plasma) same ((CH4 "CH.sub.4" ("C" adj3 "H.sub.4")) (oxygen O2 "O.sub.2") (argon Ar "Ar"))))) and (etch\$3 pattern4 trim\$4)) and ((pr photoresist photo?resist (photo		1			
"H.sub.4")) (oxygen O2 "O.sub.2") (argon Ar "Ar"))))) and (etch\$3 pattern4 trim\$4)) and ((pr photoresist photo?resist (photo					
Ar "Ar"))))) and (etch\$3 pattern4 trim\$4)) and ((pr photoresist photo?resist (photo					
and ((pr photoresist photo?resist (photo					1
					1
1 1 1 1 1 1 1 1 1 1 1 1 1 1 1 1 1 1 1					
trim\$4))) and ((pr photoresist photo?resist					
(photo near3 resist) resist) same (etch\$3		!			
pattern4 trim\$4)) same ((gas plasma) same					
((CH4 "CH.sub.4" ("C" adj3 "H.sub.4"))					
(oxygen 02 "0.sub.2") (argon Ar "Ar")))) and					
pressure)) and ((CHF3 ("CH" adj3					
"F.sub.3")("C" adj3 "H" adj3 "F.sub.3")) and					
(oxygen O2 "O.sub.2") and (argon Ar "Ar"))					

1 144	1/1/1//my whotograpist whatograpist /whato	TICDATE -	2004/06/21 14:50
- 144	(((((((pr photoresist photo?resist (photo	USPAT;	2004/06/21 14:58
	near3 resist) resist) and ((gas plasma) same	US-PGPUB	
	(hydrocarbon oxygen inert))) ((pr		
	photoresist photo?resist (photo near3		
<u>.</u>	resist) resist) and ((gas plasma) same ((CH4		
· ·	"CH.sub.4" ("C" adj3 "H.sub.4")) (oxygen O2		
	"O.sub.2") (argon Ar "Ar"))))) and (etch\$3		
	pattern4 trim\$4)) and ((pr photoresist		
,	photo?resist (photo near3 resist) resist)		
1	same (etch\$3 pattern4 trim\$4))) and ((pr		
,	photoresist photo?resist (photo near3		
1	resist) resist) same (etch\$3 pattern4		ľ
	trim\$4)) same ((gas plasma) same ((CH4		
	"CH.sub.4" ("C" adj3 "H.sub.4")) (oxygen O2		
	"O.sub.2") (argon Ar "Ar")))) and flow) and	Ì	
	((((((pr photoresist photo?resist (photo		
	near3 resist) resist) and ((gas plasma) same		
1	(hydrocarbon oxygen inert))) ((pr		
	photoresist photo?resist (photo near3		
	resist) resist) and ((gas plasma) same ((CH4		
	"CH.sub.4" ("C" adj3 "H.sub.4")) (oxygen 02		
	"O.sub.2") (argon Ar "Ar"))))) and (etch\$3		
	pattern4 trim\$4)) and ((pr photoresist		
	photo?resist (photo near3 resist) resist)		
ł	same (etch\$3 pattern4 trim\$4))) and ((pr		
	photoresist photo?resist (photo near3		
	resist) resist) same (etch\$3 pattern4		
	trim\$4)) same ((gas plasma) same ((CH4		
	"CH.sub.4" ("C" adj3 "H.sub.4")) (oxygen 02		
	"O.sub.2") (argon Ar "Ar")))) and (power		
	watt)) and ((((((pr photoresist		
į	photo?resist (photo near3 resist) resist)		
i	and ((gas plasma) same (hydrocarbon oxygen		
	inert))) ((pr photoresist photo?resist		
	(photo near3 resist) resist) and ((qas		
	plasma) same ((CH4 "CH.sub.4" ("C" adj3		
	"H.sub.4")) (oxygen O2 "O.sub.2") (argon		
	Ar "Ar"))))) and (etch\$3 pattern4 trim\$4))		•
	and ((pr photoresist photo?resist (photo		
	near3 resist) resist) same (etch\$3 pattern4		
	trim\$4))) and ((pr photoresist photo?resist		
	(photo near3 resist) resist) same (etch\$3		
İ	pattern4 trim\$4)) same ((qas plasma) same		
	((CH4 "CH.sub.4" ("C" adj3 "H.sub.4"))		
	(oxygen 02 "O.sub.2") (argon Ar "Ar")))) and		
	pressure)) and ((CH2F2 ("CH.sub.2" adj3		
İ	"F.sub.2")("C" adj3 "H.sub.2" adj3		
ĺ	"F.sub.2")) and (oxygen 02 "O.sub.2") and		
	(argon Ar "Ar"))		İ

-	95	(((((((pr photoresist photo?resist (photo	USPAT;	2004/06/21 14:59	7
	į	near3 resist) resist) and ((gas plasma) same	US-PGPUB		
		(hydrocarbon oxygen inert))) ((pr			
		photoresist photo?resist (photo near3			
	ļ	resist) resist) and ((gas plasma) same ((CH4			
	Ì	"CH.sub.4" ("C" adj3 "H.sub.4")) (oxygen O2			
		"O.sub.2") (argon Ar "Ar"))))) and (etch\$3			
		pattern4 trim\$4)) and ((pr photoresist			
		<pre>photo?resist (photo near3 resist) resist)</pre>			
		same (etch\$3 pattern4 trim\$4))) and ((pr			
		photoresist photo?resist (photo near3			
		resist) resist) same (etch\$3 pattern4			
		trim\$4)) same ((gas plasma) same ((CH4			ļ
		"CH.sub.4" ("C" adj3 "H.sub.4")) (oxygen O2			
		"O.sub.2") (argon Ar "Ar")))) and flow) and			
		((((((pr photoresist photo?resist (photo			
1		near3 resist) resist) and ((gas plasma) same			
		(hydrocarbon oxygen inert))) ((pr			
		photoresist photo?resist (photo near3			
		resist) resist) and ((gas plasma) same ((CH4			
		"CH.sub.4" ("C" adj3 "H.sub.4")) (oxygen O2			
		"O.sub.2") (argon Ar "Ar"))))) and (etch\$3			
		pattern4 trim\$4)) and ((pr photoresist			
		photo?resist (photo near3 resist) resist)			-
	•	same (etch\$3 pattern4 trim\$4))) and ((pr			
		photoresist photo?resist (photo near3			ı
-		resist) resist) same (etch\$3 pattern4			
İ		trim\$4)) same ((gas plasma) same ((CH4			
		"CH.sub.4" ("C" adj3 "H.sub.4")) (oxygen O2			
		"O.sub.2") (argon Ar "Ar")))) and (power			
		<pre>watt)) and ((((((pr photoresist</pre>			-
	1	photo?resist (photo near3 resist) resist)			
		and ((gas plasma) same (hydrocarbon oxygen			
		inert))) ((pr photoresist photo?resist			
		(photo near3 resist) resist) and ((gas			
		plasma) same ((CH4 "CH.sub.4" ("C" adj3			
		"H.sub.4")) (oxygen O2 "O.sub.2") (argon			
		Ar "Ar"))))) and (etch\$3 pattern4 trim\$4))			-
		and ((pr photoresist photo?resist (photo			
		near3 resist) resist) same (etch\$3 pattern4	j		
		trim\$4))) and ((pr photoresist photo?resist			
		(photo near3 resist) resist) same (etch\$3			
		pattern4 trim\$4)) same ((gas plasma) same			
		((CH4 "CH.sub.4" ("C" adj3 "H.sub.4"))			
		(oxygen 02 "0.sub.2") (argon Ar "Ar")))) and			
		pressure)) and ((CH3F ("CH.sub.3" adj3			
		"F")("C" adj3 "H.sub.3" adj3 "F")) and			
	1	(oxygen O2 "O.sub.2") and (argon Ar "Ar"))			

- 11 (((((((pr photoresist photo?resist (photo USPAT;	
it (/////pr photoresist photo:resist (photo oseki,	2004/06/21 14:59
near3 resist) resist) and ((gas plasma) same US-PGPUB	
(hydrocarbon oxygen inert))) ((pr	
photoresist photo?resist (photo near3	
resist) resist) and ((qas plasma) same ((CH4	
"CH.sub.4" ("C" adj3 "H.sub.4")) (oxygen O2	
"O.sub.2") (argon Ar "Ar"))))) and (etch\$3	
pattern4 trim\$4)) and ((pr photoresist	
photo?resist (photo near3 resist) resist)	
same (etch\$3 pattern4 trim\$4))) and ((pr	
photoresist photo?resist (photo near3	
resist) resist) same (etch\$3 pattern4	
trim\$4)) same ((gas plasma) same ((CH4	
"CH.sub.4" ("C" adj3 "H.sub.4")) (oxygen O2	
"O.sub.2") (argon Ar "Ar")))) and flow) and	
(((((((pr photoresist photo?resist (photo	
near3 resist) resist) and ((gas plasma) same	:
(hydrocarbon oxygen inert))) ((pr	
photoresist photo?resist (photo near3	
resist) resist) and ((gas plasma) same ((CH4	
"CH.sub.4" ("C" adj3 "H.sub.4")) (oxygen O2	
"O.sub.2") (argon Ar "Ar"))))) and (etch\$3	
pattern4 trim\$4)) and ((pr photoresist	
photo?resist (photo near3 resist) resist)	
same (etch\$3 pattern4 trim\$4))) and ((pr	
photoresist photo?resist (photo near3	
resist) resist) same (etch\$3 pattern4	
trim\$4)) same ((gas plasma) same ((CH4	
"CH.sub.4" ("C" adj3 "H.sub.4")) (oxygen O2	
"O.sub.2") (argon Ar "Ar")))) and (power	
watt)) and ((((((pr photoresist	
photo?resist (photo near3 resist) resist)	
and ((gas plasma) same (hydrocarbon oxygen	
inert))) ((pr photoresist photo?resist	
(photo near3 resist) resist) and ((gas	
plasma) same ((CH4 "CH.sub.4" ("C" adj3	
"H.sub.4")) (oxygen O2 "O.sub.2") (argon	
Ar "Ar"))))) and (etch\$3 pattern4 trim\$4))	
and ((pr photoresist photo?resist (photo	
near3 resist) resist) same (etch\$3 pattern4	
trim\$4))) and ((pr photoresist photo?resist	
(photo near3 resist) resist) same (etch\$3	
pattern4 trim\$4)) same ((gas plasma) same	
((CH4 "CH.sub.4" ("C" adj3 "H.sub.4"))	
(oxygen O2 "O.sub.2") (argon Ar "Ar")))) and	
pressure)) and ((C2H2F4 ("C.sub.2" adj3	
"H.sub.2" adj3 "F.sub.4")) and (oxygen O2	
"O.sub.2") and (argon Ar "Ar"))	

T		T	0001/05/01 11 50
- 460	(((((((((pr photoresist photo?resist (photo	USPAT;	2004/06/21 11:58
	<pre>near3 resist) resist) and ((gas plasma) same (hydrocarbon oxygen inert))) ((pr</pre>	US-PGPUB	
	photoresist photo?resist (photo near3		
	resist) resist) and ((gas plasma) same ((CH4		
	"CH.sub.4" ("C" adj3 "H.sub.4")) (oxygen O2		
	"O.sub.2") (argon Ar "Ar"))))) and (etch\$3		
	pattern4 trim\$4)) and ((pr photoresist	•	
	photo?resist (photo near3 resist) resist)		
	same (etch\$3 pattern4 trim\$4))) and ((pr		
	photoresist photo?resist (photo near3		
	resist) resist) same (etch\$3 pattern4 trim\$4)) same ((gas plasma) same ((CH4		
	"CH.sub.4" ("C" adj3 "H.sub.4")) (oxygen O2		
	"O.sub.2") (argon Ar "Ar")))) and flow) and		
	((((((pr photoresist photo?resist (photo	:	
	near3 resist) resist) and ((gas plasma) same		
i i	(hydrocarbon oxygen inert))) ((pr		
	<pre>photoresist photo?resist (photo near3 resist) resist) and ((gas plasma) same ((CH4</pre>		
	"CH.sub.4" ("C" adj3 "H.sub.4")) (oxygen O2		
	"O.sub.2") (argon Ar "Ar"))))) and (etch\$3		
:	pattern4 trim\$4)) and ((pr photoresist		
	<pre>photo?resist (photo near3 resist) resist)</pre>		
	<pre>same (etch\$3 pattern4 trim\$4))) and ((pr</pre>		
	photoresist photo?resist (photo near3		
	resist) resist) same (etch\$3 pattern4		
	trim\$4)) same ((gas plasma) same ((CH4 "CH.sub.4" ("C" adj3 "H.sub.4")) (oxygen O2		
	"O.sub.2") (argon Ar "Ar")))) and (power		
	<pre>watt)) and ((((((pr photoresist</pre>	j	
	<pre>photo?resist (photo near3 resist) resist)</pre>		
	and ((gas plasma) same (hydrocarbon oxygen		
	<pre>inert))) ((pr photoresist photo?resist (photo near3 resist) resist) and ((gas</pre>		
	plasma) same ((CH4 "CH.sub.4" ("C" adj3		
	"H.sub.4")) (oxygen O2 "O.sub.2") (argon	1	
	<pre>Ar "Ar"))))) and (etch\$3 pattern4 trim\$4))</pre>		
	and ((pr photoresist photo?resist (photo		
	<pre>near3 resist) resist) same (etch\$3 pattern4 trim\$4))) and ((pr photoresist photo?resist</pre>	İ	
	(photo near3 resist) resist) same (etch\$3		
	pattern4 trim\$4)) same ((gas plasma) same		
	((CH4 "CH.sub.4" ("C" adj3 "H.sub.4"))		
	(oxygen 02 "0.sub.2") (argon Ar "Ar")))) and		
	pressure)) and ((CH4 "CH.sub.4" ("C" adj3 "H.sub.4")) and (oxygen O2 "O.sub.2") and		
	(argon Ar "Ar"))) (((((((pr photoresist		
	photo?resist (photo near3 resist) resist)		
	and ((gas plasma) same (hydrocarbon oxygen		
	inert))) ((pr photoresist photo?resist		
	(photo near3 resist) resist) and ((gas plasma) same ((CH4 "CH.sub.4" ("C" adj3		
	"H.sub.4")) (oxygen O2 "O.sub.2") (argon		
	Ar "Ar"))))) and (etch\$3 pattern4 trim\$4))		
	and ((pr photoresist photo?resist (photo		
	near3 resist) resist) same (etch\$3 pattern4		
	trim\$4))) and ((pr photoresist photo?resist		
	<pre>(photo near3 resist) resist) same (etch\$3 pattern4 trim\$4)) same ((qas plasma) same</pre>		
	((CH4 "CH.sub.4" ("C" adj3 "H.sub.4"))		
	(oxygen O2 "O.sub.2") (argon Ar "Ar")))) and		
	<pre>flow) and (((((((pr photoresist photo?resist</pre>		
	(photo near3 resist) resist) and ((gas		
	plasma) same (hydrocarbon oxygen inert)))		
	<pre>((pr photoresist photo?resist (photo near3 resist) resist) and ((gas plasma) same ((CH4</pre>		
	"CH.sub.4" ("C" adj3 "H.sub.4")) (oxygen O2		
	"O.sub.2") (argon Ar "Ar"))))) and (etch\$3		
	pattern4 trim\$4)) and ((pr photoresist		
	photo?resist (photo near3 resist) resist)		
	same (etch\$3 pattern4 trim\$4))) and ((pr		
Search History 9/	photoresist photorresist (photo near3 resist) resist) same (etch\$3 pattern4		
C:\APPS\EAST\Workspa	CPS m 54665 Same v SP (gas plasma) same ((CH4		
	"CH.sub.4" ("C" adj3 "H.sub.4")) (oxygen O2		
			,

-	200756	pr photoresist photo?resist (photo near3 resist) resist	EPO; JPO; DERWENT;	2004/06/21 14:56
-	5332	(pr photoresist photo?resist (photo near3 resist) resist) and ((gas plasma) same	IBM_TDB EPO; JPO; DERWENT;	2004/06/21 14:56
-	4328	<pre>(hydrocarbon oxygen inert)) ((pr photoresist photo?resist (photo near3 resist) resist) and ((gas plasma) same</pre>	IBM_TDB EPO; JPO; DERWENT;	2004/06/21 14:57
		(hydrocarbon oxygen inert))) and ((gas plasma) same ((CH4 "CH.sub.4" ("C" adj3	IBM_TDB	
		"H.sub.4")) (oxygen O2 "O.sub.2") (argon Ar "Ar")))		0004/06/01 14 55
-	2710	<pre>(((pr photoresist photo?resist (photo near3 resist) resist) and ((gas plasma) same (hydrocarbon oxygen inert))) and ((gas</pre>	EPO; JPO; DERWENT; IBM TDB	2004/06/21 14:57
		plasma) same ((CH4 "CH.sub.4" ("C" adj3 "H.sub.4")) (oxygen O2 "O.sub.2") (argon		
-	2	Ar "Ar")))) and (etch\$3 pattern4 trim\$4) ((((pr photoresist photo?resist (photo near3 resist) resist) and ((gas plasma) same	EPO; JPO; DERWENT;	2004/06/21 14:58
		(hydrocarbon oxygen inert))) and ((gas plasma) same ((CH4 "CH.sub.4" ("C" adj3	IBM_TDB	
		"H.sub.4")) (oxygen O2 "O.sub.2") (argon Ar "Ar")))) and (etch\$3 pattern4 trim\$4)) and ((CH4 "CH.sub.4" ("C" adj3 "H.sub.4"))		
		and (oxygen 02 "O.sub.2") and (argon Ar "Ar"))		
-	2	<pre>(((((pr photoresist photo?resist (photo near3 resist) resist) and ((gas plasma) same (hydrocarbon oxygen inert))) and ((gas</pre>	EPO; JPO; DERWENT; IBM TDB	2004/06/21 14:58
		plasma) same ((CH4 "CH.sub.4" ("C" adj3 "H.sub.4")) (oxygen O2 "O.sub.2") (argon	IBM_IDB	
		Ar "Ar")))) and (etch\$3 pattern4 trim\$4)) and ((C2H6 ("C.sub.2" adj3 "H.sub.6")) and (oxygen O2 "O.sub.2") and (argon Ar "Ar"))	į	
-	6	<pre>((((pr photoresist photo?resist (photo near3 resist) resist) and ((gas plasma) same</pre>	EPO; JPO; DERWENT;	2004/06/21 14:58
		(hydrocarbon oxygen inert))) and ((gas plasma) same ((CH4 "CH.sub.4" ("C" adj3 "H.sub.4")) (oxygen O2 "O.sub.2") (argon	IBM_TDB	
		Ar "Ar")))) and (etch\$3 pattern4 trim\$4)) and ((CHF3 ("CH" adj3 "F.sub.3")("C" adj3		
_	2	"H" adj3 "F.sub.3")) and (oxygen O2 "O.sub.2") and (argon Ar "Ar")) ((((pr photoresist photo?resist (photo near3	EPO; JPO;	2004/06/21 14:59
		resist) resist) and ((gas plasma) same (hydrocarbon oxygen inert))) and ((gas	DERWENT; IBM_TDB	
		plasma) same ((CH4 "CH.sub.4" ("C" adj3 "H.sub.4")) (oxygen O2 "O.sub.2") (argon Ar "Ar")))) and (etch\$3 pattern4 trim\$4))		
		and ((CH2F2 ("CH.sub.2" adj3 "F.sub.2")("C" adj3 "H.sub.2" adj3 "F.sub.2")) and (oxygen		
-	1	O2 "O.sub.2") and (argon Ar "Ar")) ((((pr photoresist photo?resist (photo near3 resist) resist) and ((gas plasma) same	EPO; JPO; DERWENT;	2004/06/21 14:59
		(hydrocarbon oxygen inert))) and ((gas plasma) same ((CH4 "CH.sub.4" ("C" adj3 "H.sub.4")) (oxygen O2 "O.sub.2") (argon	IBM_TDB	
		Ar "Ar")))) and (etch\$3 pattern4 trim\$4)) and ((CH3F ("CH.sub.3" adj3 "F")("C" adj3		
_	0	"H.sub.3" adj3 "F")) and (oxygen O2 "O.sub.2") and (argon Ar "Ar")) ((((pr photoresist photo?resist (photo near3	EPO; JPO;	2004/06/21 14:59
		resist) resist) and ((gas plasma) same (hydrocarbon oxygen inert))) and ((gas	DERWENT; IBM_TDB	, 11, 12
		plasma) same ((CH4 "CH.sub.4" ("C" adj3 "H.sub.4")) (oxygen O2 "O.sub.2") (argon Ar "Ar")))) and (etch\$3 pattern4 trim\$4))		
		and ((C2H2F4 ("C.sub.2" adj3 "H.sub.2" adj3 "F.sub.4")) and (oxygen O2 "O.sub.2") and (argon Ar "Ar"))		
		(argon Ar Ar))	l	

-	9	(((((pr photoresist photo?resist (photo	EPO; JPO;	2004/06/21 15:00
		near3 resist) resist) and ((gas plasma) same	DERWENT;	
		(hydrocarbon oxygen inert))) and ((gas	IBM_TDB	
ļ		plasma) same ((CH4 "CH.sub.4" ("C" adj3 "H.sub.4")) (oxygen O2 "O.sub.2") (argon		
		Ar "Ar")))) and (etch\$3 pattern4 trim\$4))		
		and ((CH4 "CH.sub.4" ("C" adj3 "H.sub.4"))		
		and (oxygen 02 "O.sub.2") and (argon Ar		
<u> </u>		"Ar"))) (((((pr photoresist photo?resist		
		(photo near3 resist) resist) and ((gas		
		plasma) same (hydrocarbon oxygen inert)))		
		and ((gas plasma) same ((CH4 "CH.sub.4" ("C"		
		adj3 "H.sub.4")) (oxygen 02 "O.sub.2")		
		(argon Ar "Ar")))) and (etch\$3 pattern4		
	}	trim\$4)) and ((C2H6 ("C.sub.2" adj3		
·		"H.sub.6")) and (oxygen O2 "O.sub.2") and (argon Ar "Ar"))) ((((pr photoresist		
		photo?resist (photo near3 resist) resist)		
		and ((gas plasma) same (hydrocarbon oxygen	1	
	İ	inert))) and ((gas plasma) same ((CH4		
		"CH.sub.4" ("C" adj3 "H.sub.4")) (oxygen O2		
,		"O.sub.2") (argon Ar "Ar")))) and (etch\$3		
		pattern4 trim\$4)) and ((CHF3 ("CH" adj3		
1		"F.sub.3")("C" adj3 "H" adj3 "F.sub.3")) and		
		(oxygen O2 "O.sub.2") and (argon Ar "Ar")))	1	
		(((((pr photoresist photo?resist (photo		
		near3 resist) resist) and ((gas plasma) same		
		(hydrocarbon oxygen inert))) and ((gas		
		plasma) same ((CH4 "CH.sub.4" ("C" adj3 "H.sub.4")) (oxygen O2 "O.sub.2") (argon		
		Ar "Ar")))) and (etch\$3 pattern4 trim\$4))		
		and ((CH2F2 ("CH.sub.2" adj3 "F.sub.2")("C"		
		adj3 "H.sub.2" adj3 "F.sub.2")) and (oxygen		
		02 "0.sub.2") and (argon Ar "Ar"))) (((((pr		
		photoresist photo?resist (photo near3		
		resist) resist) and ((gas plasma) same		
		(hydrocarbon oxygen inert))) and ((gas		
		plasma) same ((CH4 "CH.sub.4" ("C" adj3		
		"H.sub.4"))		
		and ((CH3F ("CH.sub.3" adj3 "F")("C" adj3		
		"H.sub.3" adj3 "F")) and (oxygen O2		
		"O.sub.2") and (argon Ar "Ar")))		
-	325112		USPAT;	2004/06/21 16:43
		resist) resist	US-PGPUB	
-	11384	thin\$4 near5 (pr photoresist photo?resist	USPAT;	2004/06/21 15:53
		(photo near3 resist) resist)	US-PGPUB	
-	20039		USPAT;	2004/06/21 15:53
	10479	(photo near3 resist) resist)	US-PGPUB	2004/06/21 15 54
-	104/9	(thin\$4 near5 (pr photoresist photo?resist (photo near3 resist) resist)) and (etch\$3	USPAT; US-PGPUB	2004/06/21 15:54
		trim\$4 pattern\$4)	US-FGFUB	
_	1618	1	USPAT;	2004/06/21 16:07
	-525	(photo near3 resist) resist)) and (etch\$3	US-PGPUB	
		trim\$4 pattern\$4)) and ((argon Ar) and		
		(oxygen 02 "0.sub.2"))	1	
-	337	(((thin\$4 near5 (pr photoresist photo?resist	USPAT;	2004/06/21 15:56
		(photo near3 resist) resist)) and (etch\$3	US-PGPUB	
ļ		trim\$4 pattern\$4)) and ((argon Ar) and		
		(oxygen 02 "0.sub.2"))) and (CHF3		
_	405	"CHF.sub.3" ("C" adj3 "H" adj3 "F.sub.3")) (pr photoresist photo?resist (photo near3	IICDATT.	2004/06/21 16:06
-	405	resist) resist) and (micro near3 load\$3)	USPAT; US-PGPUB	2004/00/21 16:06
-	105		USPAT;	2004/06/21 16:43
		resist) resist) and (micro near3 load\$3))	US-PGPUB	
		and ((argon Ar) and (oxygen 02 "0.sub.2"))		
_	200756		EPO; JPO;	2004/06/21 16:43
		resist) resist	DERWENT;	
			IBM_TDB	
-	517		EPO; JPO;	2004/06/21 16:43
		resist) resist) and ((argon Ar) and (oxygen	DERWENT;	
	L	02 "O.sub.2"))	IBM_TDB	<u> </u>

			,	
-	3	((pr photoresist photo?resist (photo near3	EPO; JPO;	2004/06/21 16:44
		resist) resist) and ((argon Ar) and (oxygen	DERWENT;	
		O2 "O.sub.2"))) and (micro near3 load\$3)	IBM_TDB	
-	919	\ \ \ \ \ \ \ \ \ \ \ \ \ \ \ \ \ \ \	USPAT;	2004/09/30 14:31
		resist) resist) and (etch\$3 pattern4	US-PGPUB	
		trim\$4) and (gas plasma) and ((CH4		
		"CH.sub.4" ("C" adj3 "H.sub.4")) and (oxygen		
		02 "O.sub.2") and (argon Ar "Ar"))		<u> </u>
-	63	((pr photoresist photo?resist (photo near3	USPAT;	2004/09/30 14:36
		resist) resist) and (etch\$3 pattern4	US-PGPUB	
		trim\$4) and (gas plasma) and ((CH4	Ì	
1		"CH.sub.4" ("C" adj3 "H.sub.4")) and (oxygen		
		02 "O.sub.2") and (argon Ar "Ar"))) and		
}		(critical near3 dimens\$3)		
-	39	· ·	USPAT;	2004/09/30 14:20
		resist) resist) same (etch\$3 pattern4	US-PGPUB	
		trim\$4) and (gas plasma) same ((CH4	00 0000	
	İ	"CH.sub.4" ("C" adj3 "H.sub.4") hydrocarbon)		
		same (oxygen O2 "O.sub.2") same (argon Ar		
		"Ar"))) and (critical near3 dimens\$3)		
<u>-</u>	3		EPO; JPO;	2004/09/30 14:37
		resist) resist) and (etch\$3 pattern4	DERWENT;	2004,03,30 14.37
		trim\$4) and (gas plasma) and ((CH4	IBM TDB	
		"CH.sub.4" ("C" adj3 "H.sub.4")) and (oxygen	1511_155	
İ		O2 "O.sub.2") and (argon Ar "Ar"))		
l _	81834		EPO; JPO;	2004/09/30 14:36
-	01034	(CD (CITCICAL MEALS CIMEMS\$3))	DERWENT:	2004/09/30 14:36
	1		IBM TDB	
	1637	((CD (gritigal noar) dimong(2))) and (nr		2004/00/20 14:27
-	103/	, , ,	EPO; JPO;	2004/09/30 14:37
	1	photoresist photo?resist (photo near3	DERWENT;	
	760	resist) resist)	IBM_TDB	2004/00/20 11 11
-	/69	(((CD (critical near3 dimens\$3))) and (pr	EPO; JPO;	2004/09/30 14:41
	İ	photoresist photo?resist (photo near3	DERWENT;	
		resist) resist)) and (pattern\$4 etch\$3	IBM_TDB	
	221	trim\$4)		
_	304		USPAT;	2004/09/30 14:43
		resist) resist) same (etch\$3 pattern4	US-PGPUB	
		trim\$4) and (gas plasma) same ((CH4		
		"CH.sub.4" ("C" adj3 "H.sub.4") hydrocarbon)		
		same (oxygen O2 "O.sub.2") same (argon Ar		
	<u> </u>	"Ar"))		